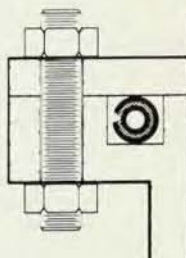


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letters

tutions with data not favorable on most of these factors would be more able to work toward improvement of their situations, if given nationwide data for comparison. Ultimately the results could be tabulated in parallel with the existing AIP directory of all institutions that teach physics. Persons using it could make more careful assessment of open positions, and achieve greater compatibility with the institution at which they choose to work.

JOHN H. MAULDIN
Winona State University
Minnesota

4/4/80

Chicago and ERA

As the head of a physics department with significant women enrollment—30% overall and nearly 40% of the freshman and sophomore classes—I took particular note of the full-column ad of the Optical Society of America in the Calendar Section in July, which urges our participation with them at the Annual APS Meeting in Chicago, 13-17 October 1980.

It seems appropriate to reiterate a stance that I took in these pages a few years ago.

No! I will not join with some colleagues at the Chicago meeting. In fact, I choose not to attend any function in Chicago or in Illinois or in any other State that refuses to ratify the ERA.

I am disappointed, but not surprised, that the APS continues to schedule Society events in non-ratifying states.

In lieu of any large-scale action, I hope that colleagues who share these feelings will strike a small blow for human rights by joining with me and others in passing up the Chicago meeting and other activities in Illinois, Louisiana, Florida, Nevada and so on.

GERALD A. FISHER

San Francisco State University

8/4/80

San Francisco, California

More on microfabrication

In two recent letters concerning the use of ion beams for lithography, the question of the relative sensitivity of polymer resists to ions versus electrons was raised (April, page 13). Our results¹ do not support the conclusions reached by R. Spohr and B. E. Fisher. We agree with them that as the deposited energy per particle increases, that is, as dE/dX increases, the exposure dose decreases as expected. Thus fewer ions are required to expose a resist than electrons, since each ion deposits more energy than an electron. However, we have found that the dose decreases nonlinearly as dE/dX increases. Thus the more fundamental measure of resist sensitivity—namely deposited energy